

## High density silane plasma for amorphous silicon coating

**Citation for published version (APA):**

Meeusen, G. J., Dahiya, R. P., Sanden, van de, M. C. M., & Schram, D. C. (1992). High density silane plasma for amorphous silicon coating. In *Plasma 92 : 7th national symposium on science and technology of plasma of Plasma Science Society of India, Bombay, 3-7 November, 1992 : Abstracts* (pp. 258)

**Document status and date:**

Published: 01/01/1992

**Document Version:**

Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

**Please check the document version of this publication:**

- A submitted manuscript is the version of the article upon submission and before peer-review. There can be important differences between the submitted version and the official published version of record. People interested in the research are advised to contact the author for the final version of the publication, or visit the DOI to the publisher's website.
- The final author version and the galley proof are versions of the publication after peer review.
- The final published version features the final layout of the paper including the volume, issue and page numbers.

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## HIGH DENSITY SILANE PLASMA FOR AMORPHOUS SILICON COATING

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### Abstract

Amorphous silicon films of solar cell quality are deposited using silicon plasma. The growth rate of the film, which is one of the cost determining factors, has significant dependence on the plasma density and its composition. High density, hydrogen rich plasma is used to deposit 500 nm thick films of amorphous silicon in 5s. The film growth is monitored with in - situ ellipsometry. Emmision spectroscopy and double probe measurements have been used to characterise the plasma. The substrate temperature and potential are also monitored continuously during the film deposition. Since impurity in the chamber can vitiate the film properties, clean background pressure of  $3 \cdot 10^{-6}$  mbar is attained by means of a turbomolecular pump. Moreover, load - lock arrangement is used for loading and unloading the substrate and this has proved highly beneficial for maintaining the clean working conditions in the chamber. The entire process is computer controlled. Film properties like temporal variation of oxygen concentration, refractive index, band gap and photoconduvtivity are also studied.

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